Dipartimento di Scienze Biologiche, Geologiche e Ambientali



FishMed-PhD Teaching week 2022



Electron Microscopy, theory, instrumentation and practical examples

Giovanni Valdrè Università di Bologna

Microscopy facilities at BiGeA







SEM



Available soon: > Atomic Force Microscopy



Environmental (P, T, gas-type, mech, elect, etc) Scanning Electron Microscopy



Vacuum modes:

- High vacuum
- Low vacuum
- Environmental-SEM
- < 6x10⁻⁴ Pa (~ 5x10⁻⁶ torr)
- up to 200 Pa (~1.5 torr)
- Intal-SEM up to 4000 Pa (~30 torr) N_2 up to 2700 Pa (~20 torr) H_2O

Gas-type: most commonly air or water vapour, but also nitrogen.

In situ studies:

-25°C to 1400°C (Peltier and heating stages).

Environmental (P, T, gas-type, mech, elect, etc) Scanning Electron Microscopy



Simultaneous acquisition and display of images from multiple detectors and detector segments => reducing beam exposure.

- Beam current: 1 pA 200 nA
- Accelerating voltage: 200 V 30 kV
- Landing energy: 20 eV 30 keV
- Magnification: 6 2500000×
- Eucentric goniometer stage with a wide tilt range (105°)
- Multi-sample SEM holder (e.g., 18 stubs)

Environmental (P, T, gas-type, mech, elect, etc) Scanning Electron Microscopy



Environmental (P, T, gas-type, mech, elect, etc) Scanning Electron Microscopy



ELECTRON – MATTER INTERACTION

- Important to understand electron microscopy and related instrumentation;
- Important to understand materials.

Knowledge of materials properties



Tour Eiffel Paris

Year: 1889

Height: 324 m

Made of wrought iron

Yield stress: 100-200 MPa Sky Tree - Tokyo





The resolution progression of cryo-EM, illustrated by a representation of **glutamate dehydrogenase** with an increasing level of detail from left to right. For a protein of this size, 334 kDa, the **1.8 Å resolution** to the right could only be achieved after 2012/13.

Year: 2012

Height: 634 m

Made of weldable highstrength steel

Yield stress: 630 MPa

Kanamycin antibiotic on bacteria – Evanescent field

- SEM
- Scanning Probe (AFM-SPM)
- Optics



E. Coli bacterium

Antigen-antibody grafted onto a glass slide

Nanometric membrane vibrations



Kanamycin antibiotic

t = 0s

t = 10min

t = 20min

t = 30min

Worth to be noted !

- Nobel Prize in Chemistry 2017
 - to Jacques Dubochet, Joachim Frank and Richard Henderson
 - for developing cryo-electron microscopy for the high-resolution structure determination of biomolecules in solution (~ 1.8 Å)
- Nobel Prize in Chemistry 2014
 - to Eric Betzig, Stefan W. Hell and William E. Moerner
 - for the development of super-resolved fluorescence microscopy Photon Optics - Stimulated emission depletion, called STED (~ 20 nm)
- Nobel Prize in Physics 1986
 - to Ernst Ruska
 - for his fundamental work in electron optics, and for the design of the first electron microscope
 - to Gerd Binning and Heinrich Rohrer
 - for their design of the scanning tunneling microscope

Summary

Dipping into history

High Resolution and improved spectroscopy

Applications

The diffraction limit → rush for ultrashort wavelength!

Visibile light: 400 nm (violet) – 700 nm (red)

• Spatial resolution: diffraction limit $d = \lambda/(2 n \cdot \sin \theta) \ge \lambda/2$



1/2 wavelength of light

Ernst Abbe (1873)

• Objective – numerical aperture $(n \cdot \sin \theta)$



Everything has its Wavelength for Bragg Reflection!

 $\lambda = hc/E$ (photons); $\lambda = h/\sqrt{(2mE)}$ for slow particles

Characteristic X-rays Moseley (1914) ~ 1Å

Low energy electrons High energy electrons <u>Davisson (1927)</u> <u>Thomson (1927)</u> $\sim 1 \text{\AA}$ $\sim 0.1 \text{\AA}$

Thermal He atoms Thermal neutrons Esterman, <u>Stern</u> (1930) $\sim 1 \text{\AA}$ Wollan, <u>Shull</u> (1945-6) $\sim 2 \text{\AA}$ Technological frontiers in the developments of Electron Microscopy and other microscopy methods (only to cite a few ...)

- Aberration-corrected TEM
- Aberration-corrected energy filtered TEM
- Dedicated STEM
- Environmental TEM
- Environmental SEM with STEM and EBSD and SDD-EDS
- Dual Beam FIB
- Scanning Probe Microscopy (SPM)
- Stimulated Emission Depletion (STED) Microscopy

Summary

Dipping into history

High Resolution and improved spectroscopy

Applications

Progressive Development of TEM Imaging

Z-contrast

CCD-EELS Detector

Image





Harald Rose



Max Haider



A long saga and continuing revolution!

Not "just" the expected improved spatial resolution!

Visibility of light atoms in negative C_s HREM

Much greater probe current in STEM

Reduced depth of field

Production of improved ancillary equipment – ETEM



Ondrej Krivanek

More efficient use of other signals – EELS, X-ray, SE?

Over 500 aberration-corrected instruments sold!

Move towards more centralised facilities?

Aberration-corrected Projection Images

Negative C_s imaging of O in SrTiO₃ Jia et al Science 2003, 299, 870



Calc.

No signs of surface reconstruction !

NOTES

Plasmon imaging was already an old subject but really took off in the region < 3eV for Au and Ag.

At these and even lower energies would better space and energy resolution be useful ?

Plasmonic Euphoria!

Nelayah et al. Nature Physics 3 (2007) 348



Nion Super STEM -

new prospects for ultra low energy EELS



Vibrational EELS for Guanine

Rez et al (2016) Nature Comms. (10 March issue)



Guanine crystal vacuum region for spectroscopy EELS spectrum at point 4 compared with published IR data for guanine Decrease of different loss peaks with increasing impact parameter

Ionisation damage is greatly suppressed at these large impact parameters

FEG – ESEM – STEM

Field Emission Gun

Environmental Scanning Electron Microscopy

Scanning Transmission Electron Microscopy

SEM – an outline of history

1895/97 J. J. Thomson discovers the electron.

- 1924 H. L. De Broglie describes the dual nature of matter: $p = h/\lambda$
- ~1926 Axial electromagnetic fields are shown to behave as "lenses" for charged particles
 The first cathode-ray tubes (CRT) are built.
- 1934 E. Ruska: first TEM prototype.
- 1937 M. Von Ardenne builds the first scanning microscope (STEM).
- ~1950 The first SEM prototype is built by Dennis Mc Mullan, under the supervision of Prof. Charles Oatley at the Cavendish Laboratory in Cambridge.

(Prof. Castaing develops the first microanalytical system in France using electronic excitation and characteristic X-ray detection)

- ~1955 The first commercial SEM is sold to study "FIBRES" at the Paper Industry of Canada.
- ~1985 Dr. Danilatos at the New South Wales University, Sydney, develops the first gaseous detector for ESEM.

~2000 Prof. Athene Donald, Cavendish Laboratory, Cambridge (UK): investigations on basic physics of ESEM.

SCANNING ELECTRON MICROSCOPE (SEM)





SEM – FEI XL30s

SEM - Hitachi S-3000N



SEM - JEOL 5800LV

ELECTRON – MATTER INTERACTION SEM-ESEM

SEM: imaging and spectroscopy

Imaging lateral variations of intensity Spectroscopy X-ray energy distributions



[mica, 4 kV, 0.2 torr, 10 mm, $V_e = 550$ V, 2000 I. sec]



SEM: electron imaging

- SE imaging
- BSE imaging



Secondary electrons (SE)

Low energy (< 50 eV). High spatial resolution (~ 1 nm). Toporgaphic contrast.

Backscattered electrons (BSE) High energy (50 eV \rightarrow E_{beam}). Resolution depends on the beam energy. Contrast by atomic number.







Information:

Lateral distribution of elements.



Cement



The merits of SEM

High spatial resolution (limit: ~ 1nm) High magnification

High depth of field

Easy sample preparation, but must be

high vacuum tolerant and conductive!

Digital image (per pixels)



VI century Ravenna mosaic fragment to illustrate the concept of pixel or image element.

An ordered sequence of pixels (e.g. according to parallel lines) provides a quantized image.





Contrast $C = (S_i - S_{i+1})/S_i = \Delta S_i/S_i$

Empirical criterion of Rose

$$\Delta S_i / S_i > 5\%$$

Electrons-matter interaction

EDS microanalysis in SEM-ESEM - STEM



Scheme of a conventional SEM



Types of sources

- THERMO-ELECTRONIC EMISSION
- FIELD EMISSION FIELD EFFECT

Sources: thermo-electronic emission



Current Density Thermionic cathodes

$$j_c = AT_c^2 \exp(-\varphi/kT_c)$$

(Richardson)

where,

- K Boltzmann constant
- T_C cathode temperature
- A ~ 120 A K⁻² cm⁻² cathode material constant
- ϕ $\,$ work function $\,$

Emission by field effect





- Emission due to the ability to extract electrons from a sharp Tungsten monoblock by strong electric fields.
- Radius of curvature of the crystal: 20-200 nm.
- Vacuum required: 10⁻⁷ Pa.
Field emission



Current Density Field emission

 $j = \frac{K_1 |E|^2}{\varphi} \exp\left(-\frac{K_2 \varphi^{32}}{|E|}\right)$

(Fowler - Nordheim)

Quantitative differences between FEG e thermo-el.

	Thermionic emission		Field emission
	w	LaB ₆	W
Work function ϕ	4.5 eV	2.7 eV	4.5 eV
Richardson constant A	75-120	30 A cm ⁻² K ⁻²	4
Emission current density j_c	1-3 A cm ⁻²	25 A cm ⁻²	104-105 A cm-2
Total current emitted I	10-100 µÅ		1-10 μA
Working temperature T _C	2800 K	1400-2000 K	(1000-1800 K)
Gun brightness β	5×10^{4}	3×10^{5} (15 keV)	$5 \times 10^{7} - 5 \times 10^{7}$
[A cm ⁻² sr ⁻¹]	(E = 10 keV)		(20 keV)
	$1-5 \times 10^{5}$		$2 \times 10^{8} - 2 \times 10^{6}$
	(100 keV)		(100 keV)
$J = dI/d\Omega [A \text{ sr}^{-1}]$	$\simeq 10^{-2}$		$= 10^{-4}$
Crossover diameter d _e	20–50 µm	10–20 μm	5-10 nm
	(hairpin)		
	10-30 µm (pointed cathode)		
Energy width ΔE	1-2 eV	0.5-2 eV	0.2-0.5 eV
Lifetime	25 h	150-200 h	-
Vacuum	10^{-2} -10 ⁻³ Pa	10 ⁻³ -10 ⁻⁵ Pa	10 ⁻⁷ -10 ⁻⁸ Pa
1 1	$(1 \text{ Pa} = 1 \text{ N m}^{-2} = 10^{-2} \text{ mbar})$		



Composite material/polycrystalline/metals, alloys, minerals, bio-minerals, corals

Mineralogical thin section, micro-nano crystalline materials



WARNING Electron – matter interaction



Attention

Caveat: SEM-EDS-EDS measurement strategy by Monte Carlo micro- and nanoanalysis simulations

SEM-EDS quantitative micro-nanoanalysis of ultrathin layers and submicrometric particles

Quantitative micro-analysis by SEM-EDS may suffer from systematic errors because of small object thickness (< $1 \mu m$).

Several phenomena had to be considered:

- Elastic scattering of electrons in the finite size (mass) of the object, strongly affected by the average atomic number;
- Reduced **X-ray absorption**, mainly related to the object geometry, which influences both the length of the X-ray absorption path within the specimen, fluorescence contribution and the take-off angle;
- EDS detector sample surface configuration.

Monte Carlo SEM-EDS quantitative micro-nanoanalysis of ultrathin layers and sub-micrometric particles

This method is useful when **the dimensions of the object in analysis approaches** the ones

of the electron penetration volume (ultra-thin layers, substrates, composites, micro-nano-

objects, powder materials), for instance:

- SEM analysis of bulk and thin sections of minerals, biominerals, textures, concretions, layer superpositions and rocks;
- Study of pigments and layers in paintings;
- Study of surface protective treatments;
- Contamination and alteration layers;
- Micro- and sub-microscopic compounds and surface disomogeneity;
- Oxidized metal surfaces, etc.

X-ray generation in <u>1 μ m thick gold leaves (Au-Ag-Cu alloy)</u> in a glass matrix



X-ray generation in <u>0.2 µm thick gold leaves</u>

Beam energy: 25 keV



Trajectories of electron scattering in the cases of a centered and non-centred beam.

Glass main elements



Generation of detected x-rays as a function of position for a non-centred beam.

Glass fibre-reinforced cementitious composite

Glass fibre analysis: fibre radius of 700 nm



Secondary electrons (SE)



Scanning electron microscopy – imaging

Basic information. Size, shape, fine structure at the micrometer to nanometre scale.

Specimen types:

General: thick, bulk (millimetre to centimetre dimensions), solid, low vapor pressure (no water); conductors (at least semiconducting)

Special: microscopic particles; film(s)-on-substrate; fixed biological specimens; wet specimens (variable-pressure or environmental SEM); nonconductors with conductive coating (conventional high beam energy and high vacuum) or uncoated (low beam energy, high vacuum; or high beam energy, variable-pressure or environmental SEM)

Signals detected:

- Backscattered electrons (BSE)
- Secondary electrons (SE)
- Specimen, absorbed, induced currents (SC)

Scanning electron microscopy – imaging

Resolution (lateral):

- Conventional electron source: 10-50 nm
- Field emission electron source: 1-5 nm

Resolution (depth):

- 10-1000 nm (BSE)
- 1-10 nm (SE)

Depth of field. Selectable with final aperture: 0.1-1 unit of the image field width; high value enables stereomicroscopy for three-dimensional recognition.

Types of image information:

- Topography (SE, BSE)
- Composition (BSE)
- Crystal orientation (BSE)
- Electrical field (SE)
- Magnetic field (SE, BSE)
- Beam-induced current (SC), Cathodoluminescence (CL)

Limits of <u>conventional</u> SEM

- Samples must tolerate vacuum.
- The sample surface must have an electrical ground connection.



Hydrated materials must be dehydrated before analysis. **Insulating materials must** be covered with conductive films - dynamic in-situ experiments that break the film cannot be performed.

Artifacts from accumulation of charge in imaging with SE in high vacuum

Nylon fibers

Dust particles



T.J. Shaffner & J.W.S. Hearle, Scanning Electron Microscopy (O.M. Johari, ed.) 62 (1976). [20 kV]







Environmental Scanning Electron Microscope

Field of pressure

- Low Vacuum: until ca 1 Torr
 ESEM until ca 30 Torr
- ESEM UNTIL CA 30 TOFF



Imaging with water vapour Thermodynamic equilibria



Advantages of environmental SEM

 Samples do not necessarily have to be vacuum tolerant.

• The sample surface does not require an electrical ground connection. Samples can be solid, hydrated, or liquid.

Samples can be conductors, semiconductors or insulators.

Dynamic *in-situ* experiments (e.g., hydration-dehydration, traction, gas-surface reaction) can be performed.

Environmental SEM

- Pressure Limiting Apertures PLA.
- Differential pumping.



Mean free path of primary electrons in the gas



Two Pressure Limiting Apertures (PLA's) integrated into the final lens assembly permit vacuums as low as 50 Torr in the sample chamber while maintaining high vacuum conditions in the gun. Keeping the apertures close together at the bottom of the column minimizes the effects of electron scattering.





F



Mean free path of primary electrons in the gas





ESEM: ion generation





What if there are too many ions?

Surface potential can float positive. Reduces gas gain. Can compromise x-ray microanalysis.

SEs can be "scavenged". Reduces SE signal intensity. Can remove some contrast mechanisms.



Differential charging: charge-induced SE image contrast

Absence of metallic coating:

SEs come from the sample, not the coating. Charge-induced contrast is present in SE images.





ESEM: resolution test SE image



Gold-on-Carbon resolution standard 30 keV, Water Vapour

ESEM: electron imaging



BSE imaging The same of conventional SEM.

SE imaging

The conventional Everhart-Thornley detector does not work in a low vacuum environment...

In-situ dynamic experiments



X-ray Microanalysis

Electrons-matter interaction

EDS microanalysis in SEM-ESEM - STEM



EDS Si-Li detector



Fig. 3.8. Schematic representation of a solid state detector (SSD), X-rays enter the detector through a thin beryllium window and produce electron-hole pairs within the semi-conductor crystal. The ionisations produce pulses which are amplified by a field effect transistor (FET) built into the rear of the crystal. (Courtesy of John Wiley and Sons Inc., New York.)
Design scheme of detector in SEM chamber



Cut-off of the window of the detector



Fig. 2.3. The efficiency of three typical detectors (1 = all X-rays detected). The position of the boron K line (B_k) is indicated. —, Conventional Be window;, ultra-thin window;, no window.



Incident X-rays move electrons from the valence band to the conduction band => a hole is produced in the valence band.

If a polarization is applied between the faces of the Si crystal, the carriers are collected, producing a voltage signal proportional to the energy of the incident X-ray: <u>1 pair (e-h) for 3.8 eV.</u>

To keep electronic noise and disturbances low => low current losses => high resistivity silicon. Unfortunately, perfectly pure silicon cannot be found: usually p-type boron impurities are present which give rise to acceptor levels just above the valence band, so that a small thermal excitation is enough to occupy them (statistical thermal noise). This is obviated by adding donor atoms to neutralize acceptors: lithium is used for 1) small atomic radius (0.06 nm) 2) good conductor.

X-ray continuum spectrum

$$I_c = i_b Z \frac{(E_0 - E)}{E}$$

Kramer's equation

- I_c = intensity of the continuum
- I_{b} = beam current
- Z = mean atomic number
- E_0 = beam energy
- E = energy of interest





Siegbahn notation

Characteristic radiation

 $\Delta E = hv$

 $v = c/\lambda$





THE SIGNAL

a) EXCITATION (ionization)

The cross section Q for the excitation (knocking-out) of an internal level by an electron incident with energy E_0 is:

$$Q = \frac{cZ\ln(E_0/E_C)}{E_0E_C} \qquad [m^2]$$

 E_c = ionization energy of the level under examination;

Z =atomic number of the element;

c = constant of the level (K, L, M, etc);

Since $E_0 \propto Z^2$, the cross section is larger for elements of low atomic number.

The average number of atoms n excited by an incident electron passing through a sample of thickness t is:

$$n = Qt\rho N/A$$

(usually a small number)

 ρ = density N = Avogadro's number A = atomic weight

Example: for K-shell 10 nm thickness of Cu (100% Cu) $E_0 = 100 \text{ keV}$ $n = 2.5 \times 10^{-4}$

b) DE-EXCITATION: e⁻ AUGER or X-RAY

Return of the excited atom to the ground state through a Z-dependent competition mechanism between e⁻ Auger and X-rays.

Ionization cross section as a function of U (overvoltage E₀/E_c)



$$\sigma = \frac{cZ\ln(E_0/E_C)}{E_0E_C} \quad [m^2]$$

 E_0 energy of incident electrons, E_c ionization energy of the element, c level constant (K, L, M, etc)

There is poor X-ray production for low Z elements, despite the ionization cross sections are favourable: almost all de-excitations go to Auger electrons.

Hence, EDS limitation to high atomic numbers. High EELS capacity for low atomic numbers.

ω

Fluorescence yield

 $\omega = \frac{Z}{Z^4 + C}$



 $C \sim - 10^8$ for excitations of level L 10⁹ for excitations of level M

E.g. C (Z=6); $\omega = 1\%$ (K) Zr (Z=40); $\omega = 72\%$ (K)

PROCESSING OF EDS SPECTRA

Necessity of spectra processing for qualitative and quantitative purposes. Because it can occur:

- 1. PARTIAL OVERLAPPING of ANALYTICAL LINES
- 2. CALCULATION AND SUBTRACTION of the BACKGROUND

AN EDS SPECTRUM CAN BE THINKED AS THE SUM OF 3 FACTORS:

- 1. ANALYTICAL LINES
- 2. BREMSSTRAHLUNG (BACKGROUND)

3. NOISE -

statistical fluctuation proper of X radiation instrumental noise (DARK CURRENT)



Thus free from electronic noise problems, the efficiency of the detection system and the geometric arrangement, the MEASURED INTENSITY becomes the TOTAL EMITTED INTENSITY.

To TRACE BACK TO THE CONCENTRATION OF THE ELEMENTS ANALYZED, WE MUST TAKE INTO ACCOUNT:

I) ABSORPTION and FLUORESCENCE

of the X radiation generated within
the sample and subsequent

then

II) NECESSARY KNOWLEDGE OF THE PHYSICAL PHENOMENA OF RADIATION GENERATION AND ELECTRONIC BACKDIFFUSION OF THE PRIMARY BEAM TO ESTABLISH A CORRECT CORRESPONDENCE BETWEEN X RADIATION OF PRIMARY GENERATION AND CONCENTRATION OF THE ELEMENT ITSELF (NOT FORGETTING THE INTENSITY OF THE CURRENT OF THE ELECTRONIC BEAM).

GENERATION AND EMISSION of X RADIATION (essential for quantitative analysis)

IMP. THE QUANTITATIVE ANALYSIS OF A SAMPLE IMPLIES ABOVE ALL THE KNOWLEDGE AND STUDY OF THE PHYSICAL, GEOMETRIC AND INSTRUMENTAL FACTORS THAT ALLOW TO TRACE BACK, FROM THE MEASUREMENT OF THE X INTENSITY DETECTED, TO THE MEASUREMENT OF THE X INTENSITY ACTUALLY GENERATED INSIDE THE SAMPLE AND FINALLY, TAKING INTO ACCOUNT THE PROCESS OF X GENERATION, TO THE COMPOSITION OF THE SAMPLE ITSELF. **

ALL THIS CAN BE SUMMARIZED FROM THE FOLLOWING SCHEME:



- direction of the quantitative analysis procedure
- ** TO THE COMPOSITION OF THE SAMPLE AREA PROBED BY THE BEAM

Microchemical quantitative analysis

Method of the continuous: (thin films)

THE X INTENSITY UNDER CONSIDERATION IS PROPORTIONAL TO THE MASS PER UNIT OF AREA OF THE ELEMENT UNDER EXAMINATION, WHEREAS THE INTENSITY OF THE CONTINUOUS RADIATION IS PROPORTIONAL TO THE MASS PER UNIT OF AREA OF THE ENTIRE SAMPLE IN THE IRRADIATED AREA. CONTINUOUS RADIATION DEPENDS ON THE AVERAGE ATOMIC NUMBER OF THE ANALYZED SAMPLE.

 I_A = Intensity of the characteristic line of element A

W = continuous radiation

K = constant of proportionality calculated using a standard with known concentration C_A

$$K = \frac{C_{ASTd}W_{STD}}{I_{ASTd}}$$

Method commonly used in <u>biology</u> since the average atomic number of the samples is almost constant.

METHOD OF THE THIN STANDARD

Relative concentration of two elements A and B in a thin binary alloy can be directly calculated from the ratio of their characteristic X intensities,

$$\frac{C_A}{C_B} = K_S \frac{I_A}{I_B}$$

Ks = constant that takes into account the relative detection efficiency of the analysis system for the 2 elements A and B; easily deducible from a STD containing the 2 elements in known quantities.

STANDARDLESS METHOD

Theoretical calculation of the constant K_s.

According to RUSS: $K_S = Q(\omega r)^T / A$

$$T = \delta e^{-C_1/E^3} \cdot \left(1 - e^{-C_2/E^3}\right) \qquad \text{(detector efficiency)}$$

 C_1 and C_2 = constants that depend on the thickness of the Detector and Be Windows

BULK STANDARDS

$$\frac{C_A}{C_B} = \left(\frac{I_A}{I_B}\right)_{spec.} \cdot \left(\frac{I_A}{I_B}\right)_{std} \cdot \frac{Q_B}{Q_A} \cdot ZAF$$

ZAF = appropriate function that takes into account the atomic number, absorption and fluorescence in the sample.

 Q_B and Q_A = are the ionization cross sections of elements B and A.

EMPIRICAL REVEALABILITY LIMITS (Silicates)

From: Dunham and Wilkinson X-ray spectrometry, 7, n° 2, 1978				SEM
15 kV	/100 Li Na ₂ O MgO Al ₂ O ₃ SiO ₂ K ₂ O CaO TiO ₂ Cr ₂ O ₃ MnO FeO NiO	veseconds Weight % 0.26 0.10 0.11 0.10 0.10 0.12 0.12 0.12 0.12	-3 KCPS	-bulk specimen > 10 μm

The values vary according to the atomic number, the type of sample, and the counting time (liveseconds).

Note that the values have been calculated for a beam acceleration potential of 15 kV (not ideal for all elements).





Electron probe x-ray microanalysis

Basic information. Elemental identification and quantification. Specimen types:

- Ideal: bulk specimen (millimetre to centimetre dimensions) polished flat to mirror finish, conductive
- Special cases: particles, foils, film(s)-on-substrate, rough surfaces, beam-sensitive specimen (especially biological), nonconductors Spectrometer types:
- Energy-dispersive x-ray spectrometer (130-eV resolution at Mn Kα)
- Wavelength-dispersive spectrometer (8-eV resolution at Mn Kα)
 Signals detected:
- Characteristic x-rays (identify elements)
- Continuum x-rays (background)

Electron probe x-ray microanalysis

Speed:

- Qualitative analysis: 10-100 s (EDS)
- Quantitative analysis: 100-500 s
- Mapping: 1000-10000 s
- Elements detected. $Z \ge 4$ (Be).
- Accuracy (95% of analyses):
- Flat, bulk target: \pm 5% relative for pure-element standards and matrix correction calculations, and \pm 25% relative for "standardless" analysis
- Particles, rough surfaces: ± 50% relative

Limits of detection:

- WDS: 10-100 parts per million (ppm)
- EDS: 1000-3000 ppm

Analytical resolution (lateral):

- Low Z: 1-5 µm
- High Z: 0.2-1 µm